

**REMARKS**

Claims 1-4 are pending in this application. By this Amendment, claims 1 and 2 are amended; and claims 3 and 4 are added.

Applicant appreciates the courtesies shown to Applicant's representative by Examiner Jackson in the November 6 personal interview. Applicant's separate record of the substance of the interview is incorporated into the following remarks.

**I. The Claims Define Patentable Subject Matter**

The Office Action rejects claims 1 and 2 under 35 U.S.C. §102(e) and alternatively §103(a) over U.S. Patent No. 5,696,386 to Yamazaki; and claims 1 and 2 under 35 U.S.C. §103(a) over Yamazaki in view of U.S. Patent No. 5,372,958 to Miyasaka et al. These rejections are respectfully traversed.

Yamazaki does not teach, disclose or suggest "an underlevel protection layer formed over the substrate and including composite layers of silicon nitride and silicon oxide; ... concentration of trapping states and crystal defects in the crystallized semiconductor layer being additive to concentrations of doping ions therein in defining the effective doping concentration," as recited in claims 1 and 2.

Instead, Yamazaki discloses that a coating consisting mainly of silicon oxide may be formed on the coating consisting mainly of aluminum nitride. Furthermore, Yamazaki does not relate to the present disclosure of a concentration of trapping states and crystal defects in the crystallized semiconductor layer being additive to concentrations of doping ions in defining the effective doping concentration as presently claimed.

Miyasaka et al. does not make up for the deficiencies of Yamazaki. Instead, Miyasaka et al. merely discloses partial coating of a substrate with a silicon oxide film. Furthermore, Miyasaka et al. does not relate to the discovery of a concentration of trapping states and

crystal defects in the crystallized semiconductor layer being additive to concentrations of doping ions in defining the effective doping concentration as presently claimed.

Even if combined, Yamazaki and Miyasaka et al. do not combine to result in the above-recited claim features.

For at least these reasons, it is respectfully submitted that claims 1 and 2 are patentable over the applied references. Applicant respectfully requests that the rejections under 35 U.S.C. §102(e) and §103(a) be withdrawn.

## II. Conclusion

In view of the foregoing, it is respectfully submitted that this application is in condition for allowance. Favorable reconsideration and prompt allowance of claims 1-4 are earnestly solicited.

Should the Examiner believe that anything further would be desirable in order to place this application in even better condition for allowance, the Examiner is invited to contact the undersigned at the telephone number set forth below.

Respectfully submitted,



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